

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination	
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Examiner		Art Unit		Page 1 of 1
JULIO J. MALDONADO		2823		

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*	B	US-6,333,257	12-2001	Aoi, Nobuo	438/626
*	C	US-6,218,317	04-2001	Allada et al.	438/780
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NON-PATENT DOCUMENTS

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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.